

Nanofocus Electron Sources

[Home / EF-1202](#)

Products

- > [RHEED](#)
- > [AUGER / XPS / EELS](#)
[/ REELS](#)
- > [Electron Sources](#)
 - > [General Purpose Electron Sources](#)
 - > [Microfocus and Nanofocus Electron Sources](#)
 - > [EM-503](#)
 - > [EM-506](#)
 - > [EM-802](#)
 - > [EF-1005](#)
 - > [EF-1201](#)
 - > [EF-1202](#)
 - > [EF-15005](#)
 - > [Electron Flood Sources](#)
 - > [High Energy Small Focus Electron Sources](#)
 - > [High Beam Power Electron Sources](#)
 - > [Low Energy Electron](#)

EF-1202

This electron gun column is designed to generate a very small spot in the nm range. It is also available as part of a complete scanning electron imaging package (SEM-package).

Key features

- Beam size (min.) 250 nm at max energy and 12 mm working distance
- Energy range 200 eV – 12 keV
- Beam current (max.) 2 μ A

Characteristics

- Working Distance (WD) 10 mm – 50 mm
- Optimum WD 12 mm nominal
- [Basic beam blanking \(optional\)](#)
- [Beam blanking, external \(optional\)](#)
- [Beam pulsing \(optional\)](#)
- [Computer control \(optional\)](#)
- [Magnetic shielding \(optional\)](#)
- [Beam scanning \(optional\)](#)
- [Microprocessor controlled beam current regulation \(optional\)](#)
- Remote control



Not all parameters can be reached simultaneously. Above specifications may change without notice. Pictures / diagrams for reference only.

Typical Applications

[AES- Depth profiling](#)

Related Products

[Filaments](#)

- Sources
- > Electron Sources for RHEED
- > Accessories for Electron Sources
- > Ion Sources
- > X-ray Source
- > Energy Analyzers & Imaging Energy Filters
- > Charged Particle Detectors
- > PEEM & IEEM
- > UHV-Systems for Surface Analysis
- > Packages for Surface Analysis
- > Data Acquisition & Instrument Control Software

- Absorbent current EM (electron microscope)
- Elastically scattered EM (electron microscope)
- UHV Scanning Electron Microscopy (SEM)
- Scanning Auger Microscopy (SAM)
- Auger Electron Spectroscopy (AES)
- Electron Energy Loss Spectroscopy (EELS) / Reflection Energy Energy Loss Spectroscopy (REELS)
- Sample imaging
- Electron Backscattered Diffraction (EBSD)
- X-ray emission analyses
- MicroRHEED

- Pre-mounted, pre-aligned cathode units
- Complete service kit
- Diagnostic box
- Scan amplifier
- Faraday cups
- Sample current measurement kit
- Gun control module
- AES and XPS energy spectrometers (ESA and DESA)
- Secondary Electron Detectors (SED) for imaging
- Scanning and imaging package (SEM Package)
- EBSD energy filter and detector

PRODUCTS

- > RHEED
- > AUGER / XPS / EELS / REELS
- > Electron Sources
- > Ion Sources
- > X-ray Source
- > Energy Analyzers & Imaging Energy Filters
- > Charged Particle Detectors
- > PEEM & IEEM
- > UHV-Systems for Surface Analysis
- > Packages for Surface Analysis
- > Data Acquisition & Instrument Control Software

APPLICATIONS

- > *In situ* Characterization
- > Surface Analysis Techniques
- > Material Growth Monitoring
- > Electron Diffraction
- > Scanning Electron Microscopy
- > Photoelectron Microscopy (PEEM)
- > Depth Profiling
- > Space Environment Simulation
- > Surface & Materials Modification

STAIB INSTRUMENTS

- > Company
- > Where to meet us
- > Contact
- > Jobs

INFORMATION

- > Home
- > Contact
- > Legal Disclosure
- > Privacy Policy

